

10/51/90

ISSUE CLASSIFICATION	
Class	Subclass

O.I.P.E.

PATENT DATE

SCANNED J. A. Q.A.

APPLICATION NO. 09/928430	CONT/PRIOR F	CLASS 430	SUBCLASS 2701	ART UNIT 1752	EXAMINER LEE, S.J.
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APPLICANTS

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TITLE

Positive-working photoresist composition and resist patterning method using same

PTO-2040
12/89

ORIGINAL

CROSS REFERENCE(S)

CLASS

SUBCLASS

CLASS

SUBCLASS (ONE SUBCLASS PER BLOCK)

INTERNATIONAL CLASSIFICATION

☐ Continued on Issue Slip Inside File Jacket

<input type="checkbox"/> TERMINAL DISCLAIMER	DRAWINGS			CLAIMS ALLOWED	
	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims	Print Claim for O.G.
<input type="checkbox"/> The term of this patent subsequent to _____ (date) has been disclaimed. <input type="checkbox"/> The term of this patent shall not extend beyond the expiration date of U.S. Patent. No. _____ <input type="checkbox"/> The terminal _____ months of this patent have been disclaimed.	_____ (Assistant Examiner) (Date)			NOTICE OF ALLOWANCE MAILED	
	_____ (Primary Examiner) (Date)			ISSUE FEE	
				Amount Due	Date Paid
	_____ (Legal Instruments Examiner) (Date)			ISSUE BATCH NUMBER	

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